# LabAdviser update: 11/5 2020

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| Updated Subject  | Contributor | Link to the updated pages |
| **Technology Research**Some project descriptions have been added:  | **Emil Ludvigsen @Nanolab****Quang Long Nguyen****@Nanolab** | [Technology\_Research/Direct\_laser\_pyrolysis](http://labadviser.nanolab.dtu.dk/index.php/LabAdviser/Technology_Research/Direct_laser_pyrolysis)[Technology\_Research/Direct\_write\_lithography\_on\_MLAs\_for\_fabrication\_of\_carbon\_micro\_tips](http://labadviser.nanolab.dtu.dk/index.php/LabAdviser/Technology_Research/Direct_write_lithography_on_MLAs_for_fabrication_of_carbon_micro_tips) |
| **Tech Forum**The latest tech forum slides have been uploaded. You can find a link from the main page of LabAdviser or here. | **Anders M. Jørgensen @Nanolab** | <http://labadviser.nanolab.dtu.dk/images/8/8a/Techforum_2020_1.pdf> |
| **Deposition of TiN**Deposition of TiN in Sputter system Lesker. A number of experiments have been performed with variations in the process parameters. The results have been analyzed with ellipsometry and XPS.TiN overview page has been updated | **Evgeniy Shkondin @Nanolab** | [Thin\_film\_deposition/Deposition\_of\_Titanium\_Nitride/Deposition\_of\_Titanium\_Nitride\_using\_Lesker\_sputter\_tool](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Titanium_Nitride/Deposition_of_Titanium_Nitride_using_Lesker_sputter_tool)[/Deposition\_of\_Titanium\_Nitride/Deposition\_of\_Titanium\_Nitride\_using\_Lesker\_sputter\_tool](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Titanium_Nitride/Deposition_of_Titanium_Nitride_using_Lesker_sputter_tool) |
| **Pyrolysis**New page: General pyrolysis processNew page: Optimized pyrolysis process for different purpose using Multipurpose Anneal Furnace | **Quang Long Nguyen @Nanolab** | [/Thermal\_Process/Pyrolysis](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thermal_Process/Pyrolysis)[/Pyrolysis/Pyrolysis\_with\_Multipurpose\_Anneal\_Furnace](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thermal_Process/Pyrolysis/Pyrolysis_with_Multipurpose_Anneal_Furnace) |
| **Topographic measurements**Added Dektak 150 to the overview page for the topographic measurements. | **Rebecca B. Ettlinger @Nanolab** | [/Characterization/Topographic\_measurement](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/Topographic_measurement) |
| **Maskless 02 aligner (MLA2)**The section on alignment has been added.  | **Thomas A Anhøj @Nanolab** | [/Aligners/Aligner:\_Maskless\_02\_processing](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Lithography/Aligners/Aligner%3A_Maskless_02_processing) |
| **Post CMP Cleaner**Equipment page on the Post CMP Cleaner has been added. | **Rune Christiansen @Nanolab** | [Wafer\_cleaning/Post\_CMP\_Cleaner](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Wafer_cleaning/Post_CMP_Cleaner) |
| **Deposition of ITO**New comparison page on ITO deposition. | **Rebecca B. Ettlinger @Nanolab** | [Thin\_film\_deposition/Deposition\_of\_ITO](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_ITO) |
| **Thin film deposition** Update of the thin film overview page. New materials have been added.  | **Rebecca B. Ettlinger, Evgeniy Shkondin @Nanolab** | [Thin\_film\_deposition#Choose\_material\_to\_deposit](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition#Choose_material_to_deposit) |
| **Sputter system Metal-oxide (PC1) and Sputter system Metal-nitride (PC3) (Cluster Lesker system)**All the materials in this two systems have been added to the respective comparison pages for these materials.The materiels are: Al, Au, Ag, Ni, Cu, Ti, Ge, Si, SiO2, Al2O3, AlN and ITO | **Rebecca B. Ettlinger @Nanolab** | You find the links to these comparison pages here: [Thin\_film\_deposition#Choose\_material\_to\_deposit](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition#Choose_material_to_deposit) |
| **Measurement of film thickness and optical constants**Added XRD as a method. | **Rebecca B. Ettlinger****@Nanolab** | [Characterization/Measurement\_of\_film\_thickness\_and\_optical\_constants](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/Measurement_of_film_thickness_and_optical_constants) |
| **Stress measurements**Added stress measurements of crystalline films using XRD | **Rebecca Ettlinger @Nanolab** | [/Characterization/Stress\_measurement](http://labadviser.nanolab.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/Stress_measurement) |

# Equipment Manuals updated in LabManager (since 6th of April):

As an approved user on a piece of equipment you have to make sure you have read and understood the latest version of the manual before using the equipment.

**Manual for aligner: Maskless 02. ver. 1.1**